

L Number	Hits	Search Text	DB	Time stamp
-	2654158	(wafer or substrate or semiconductor)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:12
-	941	((raised or lifted or lift or lifter or assend or elevator or elevated) and (lowered or dunk or desend)) same ((spray or nozzle or jet) near15 (reactor or container or receptacles or tank or basin or sink or bath or vessel))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 19:29
-	48212	(wafer or substrate or semiconductor)	USOCR	2004/04/18 19:25
-	1785	((raised or lifted or lift or lifter or assend or elevator or elevated) and (lowered or dunk or desend)) same ((spray or nozzle or jet) near15 (reactor or container or receptacles or tank or basin or sink or bath or vessel))	USOCR	2004/04/18 19:25
-	24	((wafer or substrate or semiconductor) ) and (((raised or lifted or lift or lifter or assend or elevator or elevated) and (lowered or dunk or desend)) same ((spray or nozzle or jet) near15 (reactor or container or receptacles or tank or basin or sink or bath or vessel)))	USOCR	2004/04/18 19:26
-	148	((wafer or substrate or semiconductor) ) and (((raised or lifted or lift or lifter or assend or elevator or elevated) and (lowered or dunk or desend)) same ((spray or nozzle or jet) near15 (reactor or container or receptacles or tank or basin or sink or bath or vessel)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 19:26
-	6459	((reciprocated or raised or lifted or lift or lifter or assend or elevator or upwardly or elevated or up) and (down or downwardly or lowered or dunk or desend)) same ((spray or nozzle or jet) near15 (reactor or container or receptacles or tank or basin or sink or bath or vessel))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 20:20
-	13372	((reciprocated or raised or lifted or lift or lifter or assend or elevator or upwardly or elevated or up) and (down or downwardly or lowered or dunk or desend)) same ((spray or nozzle or jet) near15 (reactor or container or receptacles or tank or basin or sink or bath or vessel))	USOCR	2004/04/18 19:31
-	565	((wafer or substrate or semiconductor) ) and (((reciprocated or raised or lifted or lift or lifter or assend or elevator or upwardly or elevated or up) and (down or downwardly or lowered or dunk or desend)) same ((spray or nozzle or jet) near15 (reactor or container or receptacles or tank or basin or sink or bath or vessel)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 19:32
-	173	((wafer or substrate or semiconductor) ) and (((reciprocated or raised or lifted or lift or lifter or assend or elevator or upwardly or elevated or up) and (down or downwardly or lowered or dunk or desend)) same ((spray or nozzle or jet) near15 (reactor or container or receptacles or tank or basin or sink or bath or vessel)))	USOCR	2004/04/18 19:32

6988	((reciprocated or raised or lifted or lift or lifter or ascend or elevator or upwardly or elevated or up) and (down or downwardly or lowered or dunk or descend)) same ((spray or nozzle or jet) near25 (reactor or container or receptacles or tank or basin or sink or bath or vessel))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 20:22
1016	((reciprocated or raised or lifted or lift or lifter or ascend or ascent or elevator or upwardly or elevated or up) same (reciprocating or down or downwardly or lowered or dunk or descent or descend)) and ((spray or nozzle or jet) near25 (reactor or container or receptacles or tank or basin or sink or bath or vessel)) and ((semiconductor or wafer or substrate) near25 (wash or washing or clean or cleaning or rinse or rinsing))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 20:27
34	((reciprocated or raised or lifted or lift or lifter or ascend or ascent or elevator or upwardly or elevated or up) same (reciprocating or down or downwardly or lowered or dunk or descent or descend)) and ((spray or nozzle or jet) near25 (reactor or container or receptacles or tank or basin or sink or bath or vessel)) and ((semiconductor or wafer or substrate) near25 (wash or washing or clean or cleaning or rinse or rinsing))	USOCR	2004/04/18 20:26
671	((reciprocated or raised or lifted or lift or lifter or ascend or ascent or elevator or upwardly or elevated or up) same (reciprocating or down or downwardly or lowered or dunk or descent or descend)) and ((spray or nozzle or jet) near25 (reactor or container or receptacles or tank or basin or sink or bath or vessel)) and ((semiconductor or wafer or substrate) near25 (wash or washing or clean or cleaning or rinse or rinsing)) and (robot or carrier or jig or traverse or carriage or car or vehicle)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 20:42
21	((reciprocated or raised or lifted or lift or lifter or ascend or ascent or elevator or upwardly or elevated or up or dip or dipping) same (reciprocating or down or downwardly or lowered or dunk or descent or descend)) and ((spray or nozzle or jet) near25 (reactor or container or receptacles or tank or basin or sink or bath or vessel)) and ((semiconductor or wafer or substrate) near25 (wash or washing or clean or cleaning or rinse or rinsing)) and (robot or carrier or jig or traverse or carriage or car or vehicle)	USOCR	2004/04/18 20:46
675	((reciprocated or raised or lifted or lift or lifter or ascend or ascent or elevator or upwardly or elevated or up or dip or dipping) same (reciprocating or down or downwardly or lowered or dunk or descent or descend)) and ((spray or nozzle or jet) near25 (reactor or container or receptacles or tank or basin or sink or bath or vessel)) and ((semiconductor or wafer or substrate) near25 (wash or washing or clean or cleaning or rinse or rinsing)) and (robot or carrier or jig or traverse or carriage or car or vehicle)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 21:38

-	21	((reciprocated or raised or lifted or lift or lifter or ascend or ascent or elevator or upwardly or elevated or up or dip or dipping) same (reciprocating or down or downwardly or lowered or dunk or descent or descend)) and ((spray or nozzle or jet) near25 (reactor or container or receptacles or tank or basin or sink or bath or vessel)) and ((semiconductor or wafer or substrate) near25 (wash or washing or clean or cleaning or rinse or rinsing)) and (robot or carrier or jig or traverse or carriage or car or vehicle)	USOCR	2004/04/18 21:38
-	2407	134/902.ccls. or 134/196.ccls. or 134/76.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 21:40
-	329	134/196.ccls. or 134/76.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 21:40
-	474	(134/902.ccls. or 134/196.ccls. or 134/76.ccls.) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or bath or vessel))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 23:24
-	7	(134/164.ccls.) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or bath or vessel))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 22:25
-	34	(134/902.ccls. or 134/196.ccls. or 134/76.ccls. or 134/164.ccls.) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or bath or vessel))	USOCR	2004/04/18 22:26
-	13	((wafer or substrate or semiconductor) near20 (reciprocate or ricprocated or reciprocating or shaken or shaken or shaking)) same ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/18 22:31
-	0	((wafer or substrate or semiconductor) near20 (reciprocate or ricprocated or reciprocating or shaken or shaken or shaking)) same ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USOCR	2004/04/18 22:35
-	0	((wafer or substrate or semiconductor) near25 (reciprocate or reciprocated or reciprocating or shaken or shaken or shaking)) same ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USOCR	2004/04/18 22:35
-	0	((wafer or substrate or semiconductor) near25 (reciprocate or reciprocated or reciprocating or shaken or shaken or shaking)) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USOCR	2004/04/18 22:36

-	91	((wafer or substrate or semiconductor) near25 (reciprocate or reciprocated or reciprocating or shaken or shaken or shaking)) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 22:49
-	0	((wafer or substrate or semiconductor) near25 (vibrating or vibrated or vibration or oscillate or oscillation or oscillating) near25 (carrier or jig or holder or support)) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USOCR	2004/04/18 22:47
-	20	((wafer or substrate or semiconductor) near25 (vibrating or vibrated or vibration or oscillate or oscillation or oscillating) near25 (carrier or jig or holder or support)) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 22:47
-	2	396/\$.ccls. and (reciprocate or reciprocated or reciprocating or shaken or shaken or shaking) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USOCR	2004/04/18 22:51
-	20	396/\$.ccls. and (reciprocate or reciprocated or reciprocating or shaken or shaken or shaking) and ((spray or jet or nozzle) near25 (bowl or reactor or container or receptacles or tank or basin or sink or bath or vessel) near25 (wash or washing or cleaning or cleaned or clean or decontaminate or rinse or rinsing))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 22:51
-	2113	134/902.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 00:04
-	2	("6624060").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 00:03
-	2	("6624060").PN.	USPAT; EPO; JPO; DERWENT	2004/04/19 00:04
-	1875	134/902.ccls.	USPAT; EPO; JPO; DERWENT	2004/04/19 03:11
-	238	134/902.ccls.	US-PGPUB	2004/04/19 02:22
-	13	134/902.ccls.	USOCR	2004/04/19 02:45
-	3	"2003105200"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 02:52

-	2	"6199567" and (jet or nozzle or spray)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:02
-	1	"20020162579" and (jet or nozzle or spray)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:02
-	71	(wafer or substrate or semiconductor) and 134/199.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:15
-	0	((single adj (wafer or substrate or semiconductor)) near15 vertical) same ((spray or jet or nozzle) near25 (wash or washing or clean or cleaning or rinse or rinsing or flushing))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:17
-	189	(single near5 (wafer or substrate or semiconductor)) same ((spray or jet or nozzle) near25 (wash or washing or clean or cleaning or rinse or rinsing or flushing))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:39
-	11	(single near5 (wafer or substrate or semiconductor)) same ((spray or jet or nozzle) near25 (wash or washing or clean or cleaning or rinse or rinsing or flushing))	USOCR	2004/04/19 03:18
-	1022	(single near5 (disc or disk or wafer or substrate or semiconductor)) and 134/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:39
-	977	(single near5 (disc or disk or wafer or substrate or semiconductor)) and 134/\$.ccls. and (wash or washing or clean or cleaning or rinse or rinsing or flushing)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:40
-	3161	(single near5 (disc or disk or wafer or substrate or semiconductor)) same (jet or nozzle or spray or spraying or sprayed)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:41
-	187	(single near5 (disc or disk or wafer or substrate or semiconductor)) same (jet or nozzle or spray or spraying or sprayed) and 134/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/19 03:53
-	9	(single near5 (disc or disk or wafer or substrate or semiconductor)) same (jet or nozzle or spray or spraying or sprayed) and 134/\$.ccls.	USOCR	2004/04/19 03:54
-	0	(single near5 (disc or disk or wafer or substrate or semiconductor)) near25 ("vertical orientation" or (horizontal near8 axis near8 rotation)) same (jet or nozzle or spray or spraying or sprayed) same (wash or washing or clean or cleaning or rinse or rinsing or flushing)	USOCR	2004/04/19 03:57
-	0	(single near5 (disc or disk or wafer or substrate or semiconductor)) near25 ("vertical orientation" or (horizontal near8 axis near8 rotation)) same (jet or nozzle or spray or spraying or sprayed) same (wash or washing or clean or cleaning or rinse or rinsing or flushing)	USOCR	2004/04/19 04:01
-	8105	circuit and 134/\$.ccls. stinson	USPAT	2004/04/19 04:02
-	378	circuit and 134/\$.ccls. and stinson	USPAT	2004/04/19 04:02
-	80	circuit and 134/\$.ccls. and stinson and rollers	USPAT	2004/04/19 04:08
-	12	"4715392" and pump	USPAT	2004/04/19 04:09